

Agenda

Micro-Optics Design and System Simulation

3 AR/VR Photonic Devices

4 Manfacturing Impact and Optical Virtual Fab

OPTICAL SOLUTIONS

A comprehensive portfolio

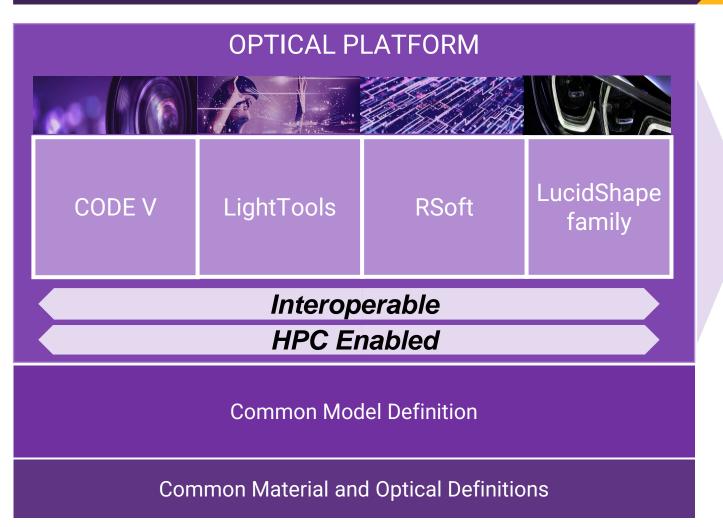
For OPTICAL design
ILLUMINATION design
PHOTONIC design
AUTOMOTIVE design
VIRTUAL prototyping

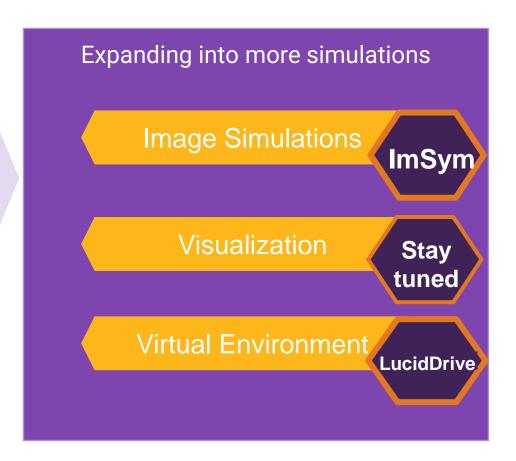
With proprietary optimization engines for ACCURACY and SPEED



The Most Advanced Optical Design & Simulations Platform

Design





Accelerate Optical Simulation

Analyzing optical systems can require substantial computing power, as analysis can require **tracing large ray sets**, **performing high-fidelity FDTD calculations**, and **performing many other intensive optical analysis mathematics**.



Faster Hardware

- CPU speed
- Multi-core CPUs
- Multi-threading
- GPU



Distributed Hardware

- Multi-CPU computers
- Multiple computers
- Multiple GPUs
- Distributed Scanning



Efficient Flows

- Learn your tool
- Leverage innovative algorithms
- Self-paced learning options
- Talk to our engineering experts

HOW CAN YOU GET YOUR JOB DONE FASTER?

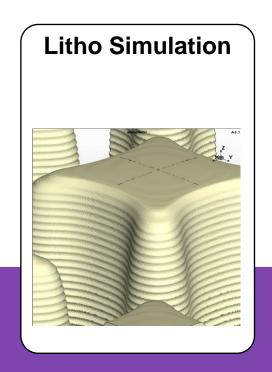
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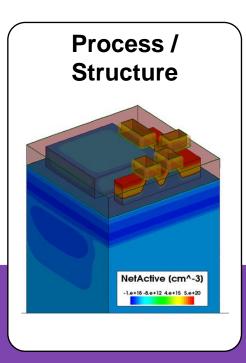
Micro-Optics Design and System Simulation

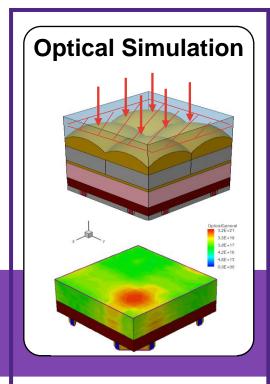
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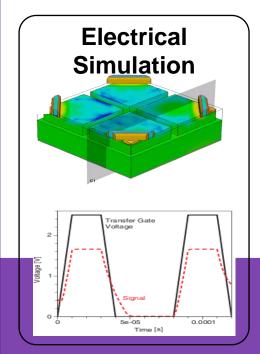
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TCAD Sentaurus – RSoft Flow Overview









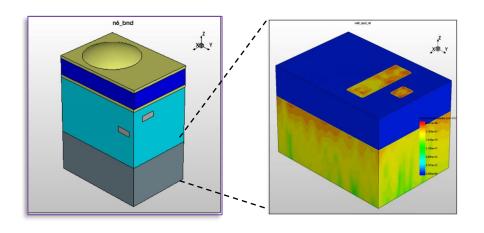
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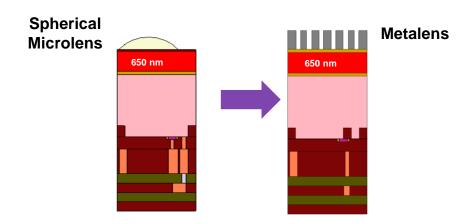
wavelength intensity rsoft_tool		SDEVICE	57/19			
0.475 0.1 DiffractMOD 0.55 0.1 FullWAVE 0.65 0.1		wavelength	intensity	rsoft_tool		
0.55 0.1 DiffractMOD DiffractM		0.475	0.1	FullWAVE		-
0.55 0.1 DiffractMOD FullWAVE				DiffractMOD		-
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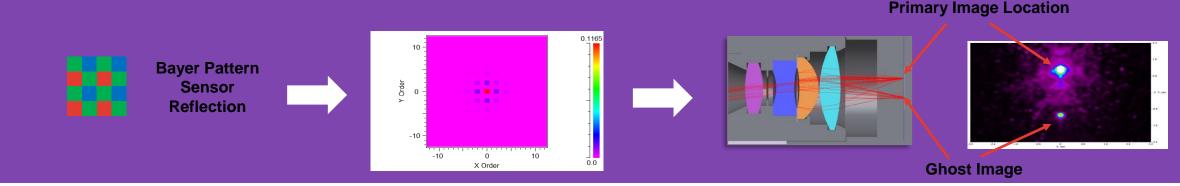
Optical Simulation for CIS

- DiffractMOD RCWA and FullWAVE FDTD to calculate reflection, transmission, absorbed photon density, BSDF, ...
- Micro-Optics variation: Replace Micro-Lens Array (MLA) with a Metalens using MOD MetaOptic designer
- Analyze stray light due to reflections from the CIS in a camera system using LightTools and Rsoft BSDF utility



Absorbed Photon Density





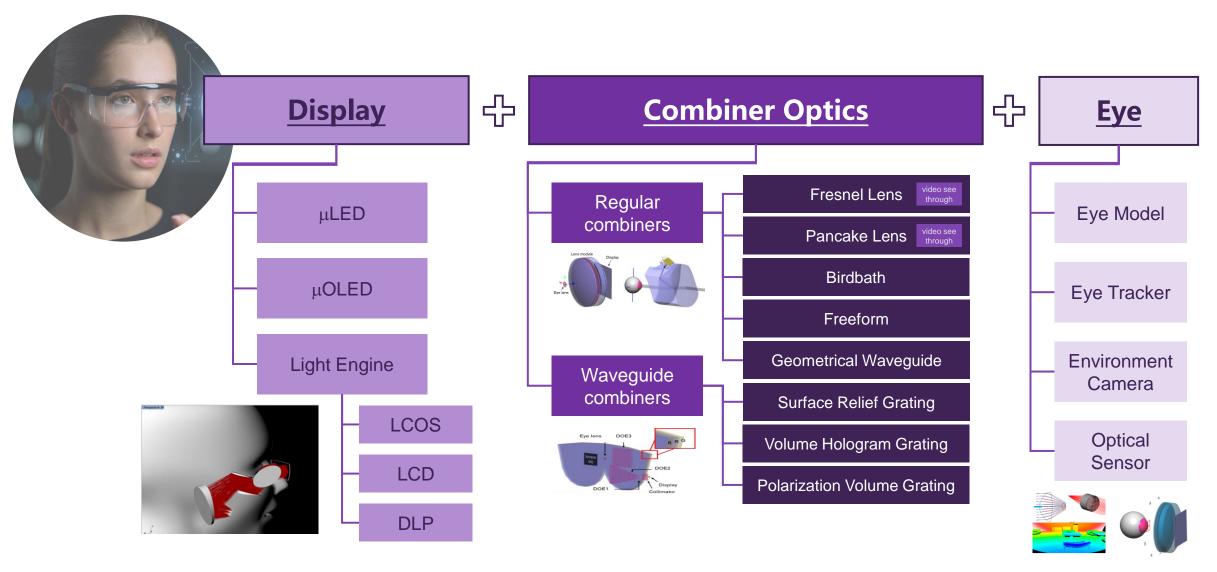
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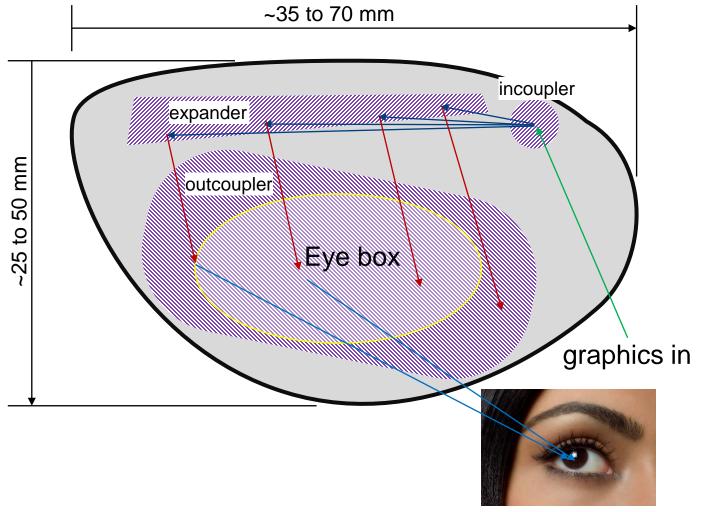
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Key Optical Systems in AR/VR Devices



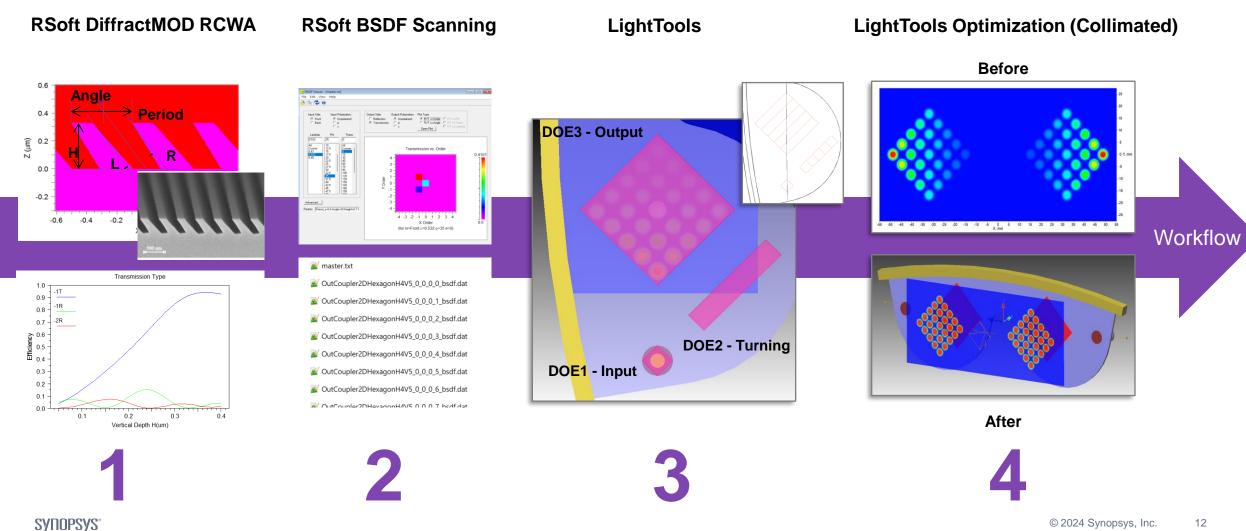
Waveguide Optical combiner

Expands graphics and places them in the eye box



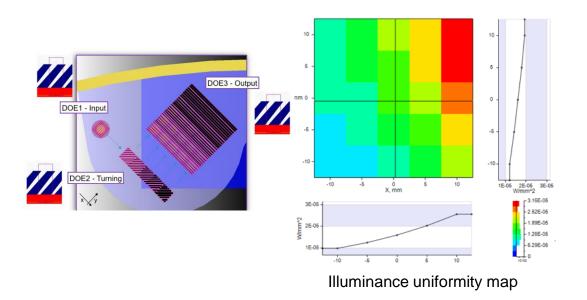
- The Waveguide Optical combiner is a series of waveguides
 - Incoupler transmits the input graphics to the expander
 - Expander magnifies the graphics and transmits them to the outcoupler
 - Outcoupler overlays the graphics on the real scene for viewing
- The eye box is the intended viewing area of the outcoupler
- Surface Relief Gratings (SRG) is a type of Diffractive Optical Elements (DOE) having a periodicity ~λ

Waveguide AR Design Flow



LightTools Design Optimization

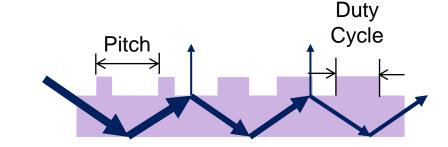
Duty Cycle Variation

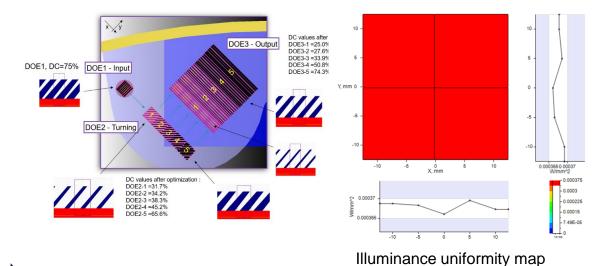


Before Optimization

Uniform DC (25 % FF)

Efficiency: 1.7%





After Optimization

Variable DC (20-70% FF)

Efficiency: 23.5%

Efficiency: light on the eye box vs incident light



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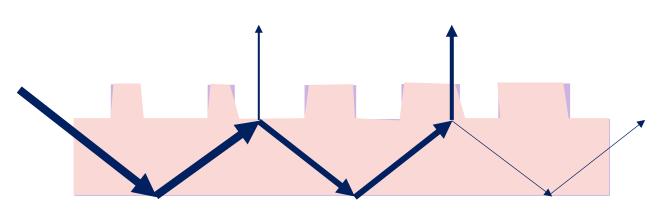
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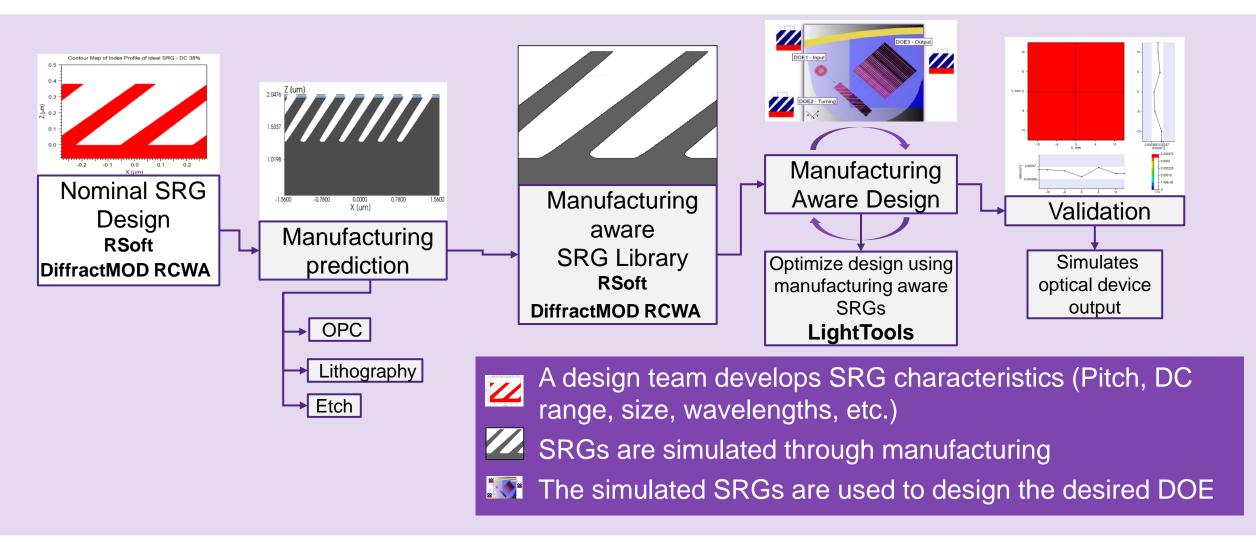
SRG After Manufacturing

Manufacturing artifacts may dramatically impact device performance

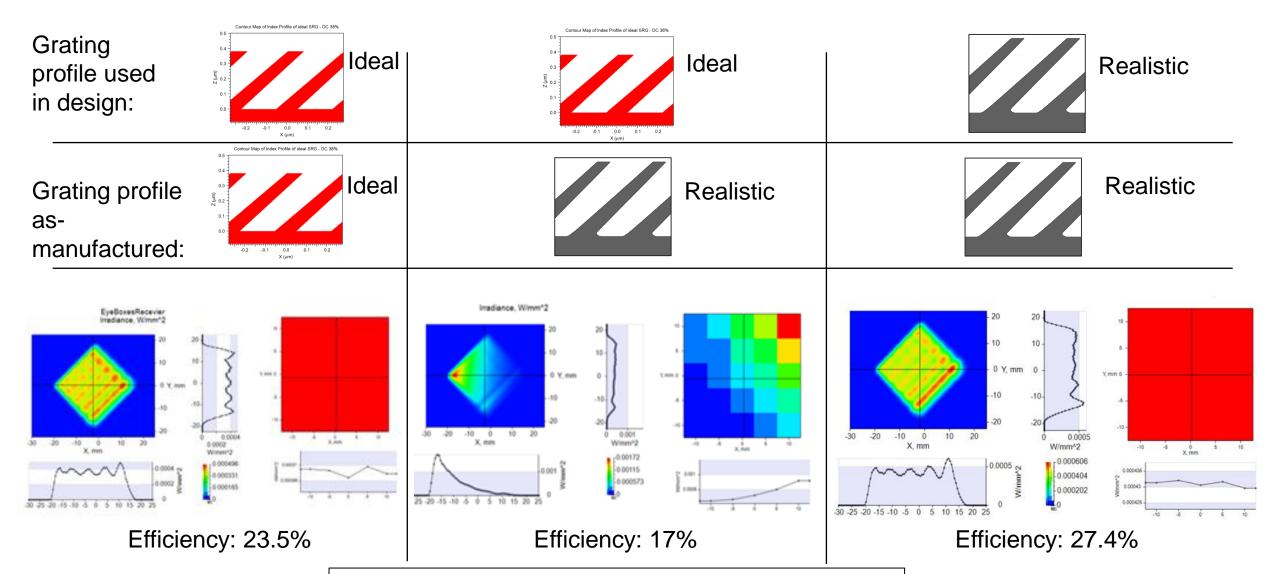


- Manufacturing produces a device that is not ideal (as the designer drew it)
 - Sidewall angles
 - Over etching
 - Rounding corners and at trench bottom
- These artifacts may result in:
 - Eye box uniformity degradation
 - Intensity loss
 - Blurred images
 - Failed devices

Manufacturing Aware Design Flow Targets First Print Correct Design



Optimizing the Design: Applying Manufacturing Simulation

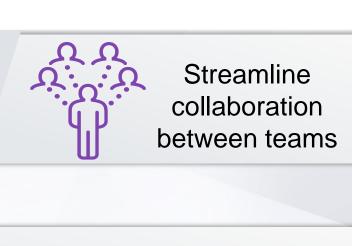




Illuminance uniformity on eye box

Conclusion

- Streamline collaboration between teams to provide useful and comprehensive flows
- Flexibility and interoperability between tools for a better system design simulation
- Cost and time reduction:
 - 1. Innovative algorithm
 - 2. Cluster computation
 - 3. Hardware acceleration
 - 4. Optical Virtual Fab





Flexibility



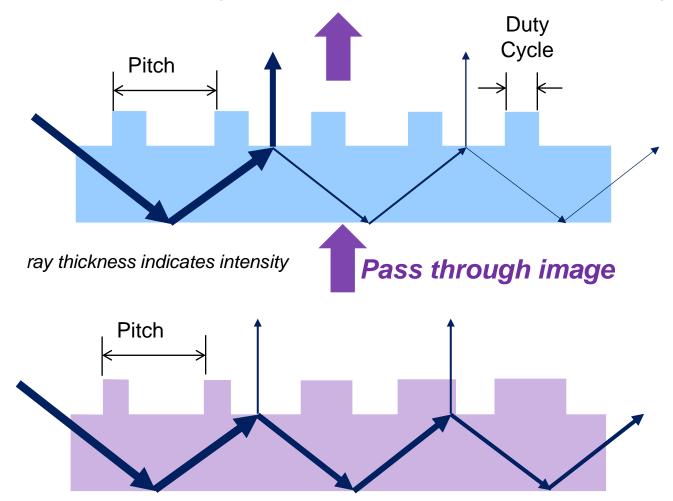
Cost/Time Reduction



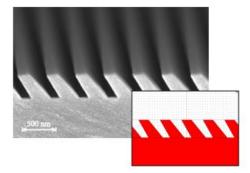
SYNOPSYS®

Surface Relief Grating Waveguide

An AR/VR strategy to combine environmental and graphical images



- SRGs are periodic structures of constant Pitch
- Pitch governs the wavelength(s) of light manipulated by the SRG
- The Duty Cycle (DC) governs reflected images
- Filling Factor (FF) = DC/Pitch
- DC is varied to balance output intensity
- Slanted gratings are more efficiently directing light than 90° gratings



Modeling SRG Manufacturing

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X (um)

Stack and Process $\lambda = 193 \text{ nm (ArF)}$ DUV Resist: 150 nm, n=1.67, k=0.015 BARC: 37 nm. n=1.67, k=0.3 0.2385 (simulated resist profile, DTL) 0.1142 -0.0100 -1.5000 SiO2: 300 nm



- RIE etch simulation to transfer pattern into SiO₂ parameters
- In collaboration with

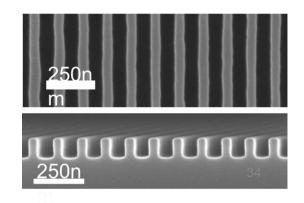
-0.7500

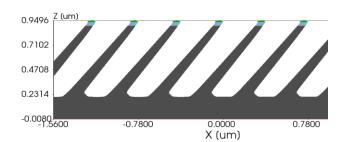


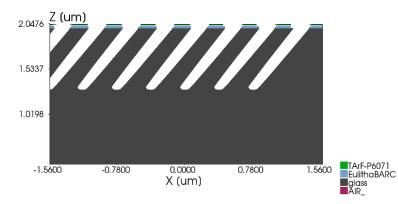
0.7500

1.5000

n=1.563, k=0







WOOLEY, Kelsey, CHALONY, Maryvonne, DAWES, Andrew MC, et al. Simulating use of displacement Talbot lithography for high volume AR waveguide manufacturing. In: DTCO and Computational Patterning III. SPIE, 2024. p. 308-318.